

**CS International 2023**

# **Underpinning the growth of gallium oxide**

**Akito Kuramata**

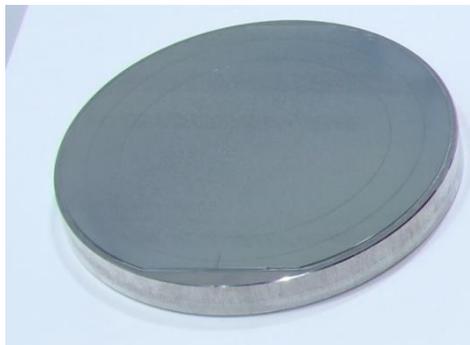


**Novel Crystal Technology, Inc.**

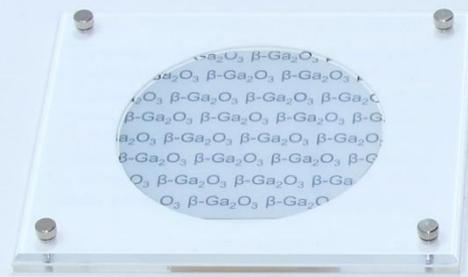
**April 19, 2023**

# Novel Crystal Technology (NCT)

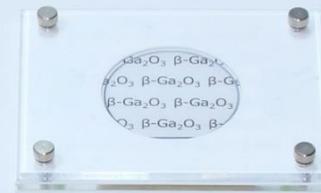
- Carve out venture from Tamura Corporation
- Established in 2015
- Located in Sayama, Saitama, Japan
- Products:
  - $\text{Ga}_2\text{O}_3$  substrates & epi wafers
  - $\text{Ga}_2\text{O}_3$  power devices (TBA)



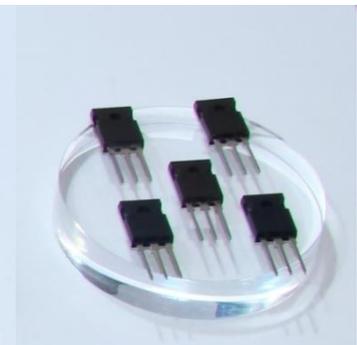
6 inch substrate



4 inch substrate



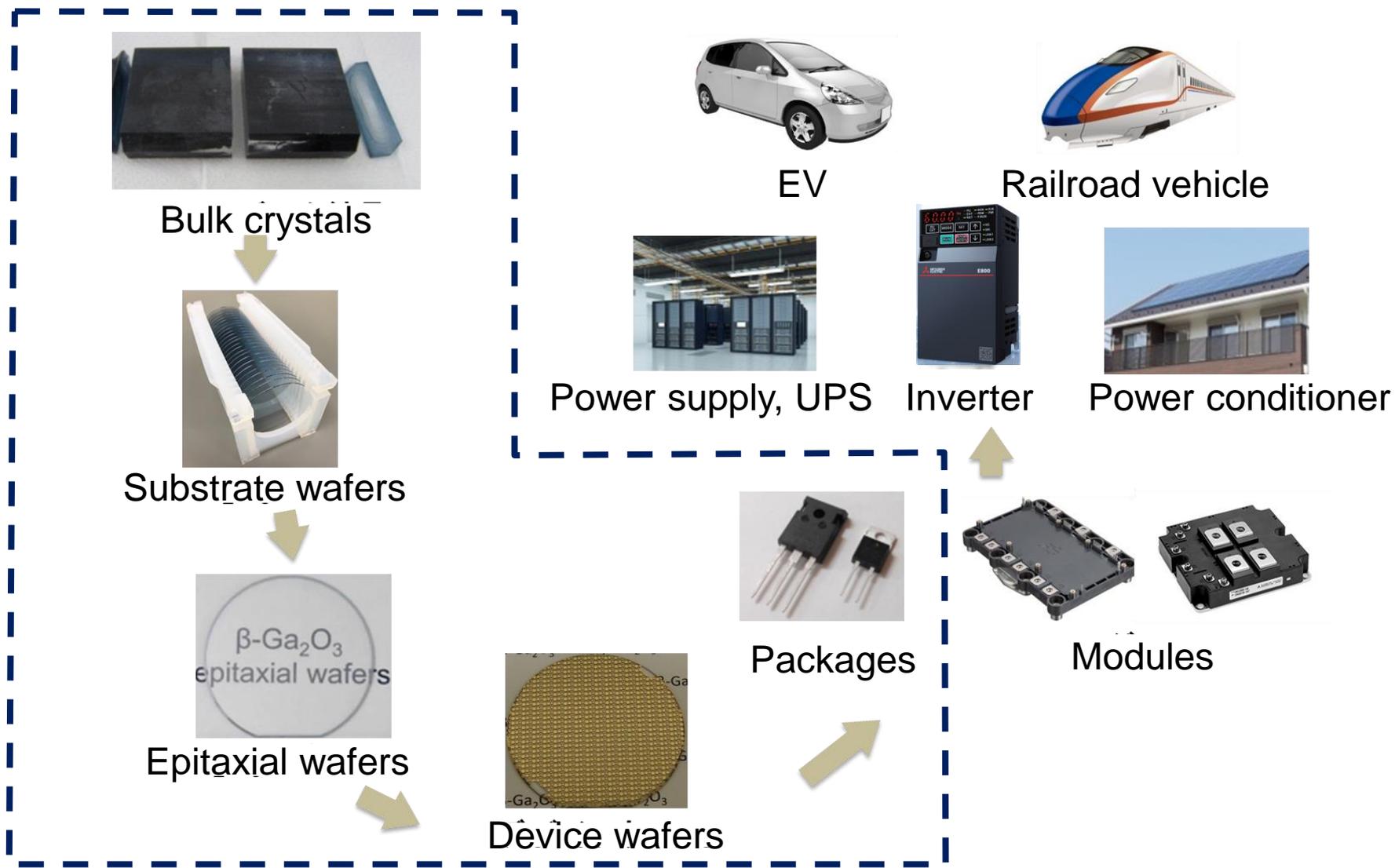
2 inch epi wafer



SBDs

# Products

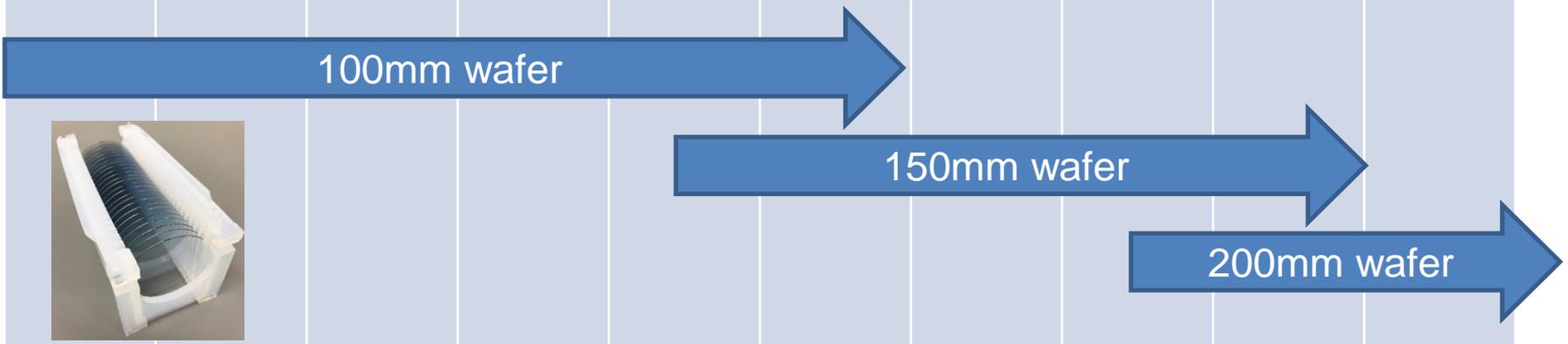
## Production flow of Ga<sub>2</sub>O<sub>3</sub> power devices



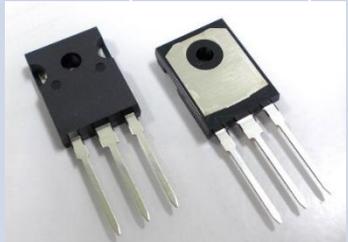
**NCT's Products**

# Product Roadmap

FY2021	FY2022	FY2023	FY2024	FY2025	FY2026	FY2027	FY2028	FY2029	FY2030
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Aiming for cost performance that surpasses SiC SBD



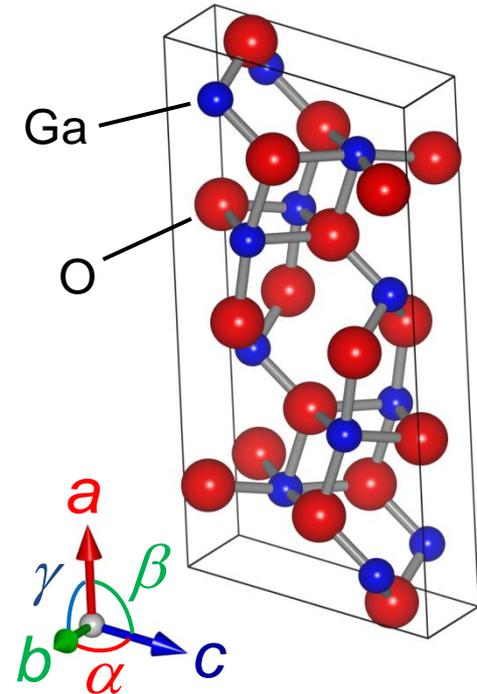
Aiming for cost performance that surpasses Si IGBT

# Features of $\text{Ga}_2\text{O}_3$

- Ultra wide bandgap semiconductor
- Bandgap: 4.5-4.8 eV
- High electric field strength: ~8 MV/cm
- Bulk crystals can be grown from melt



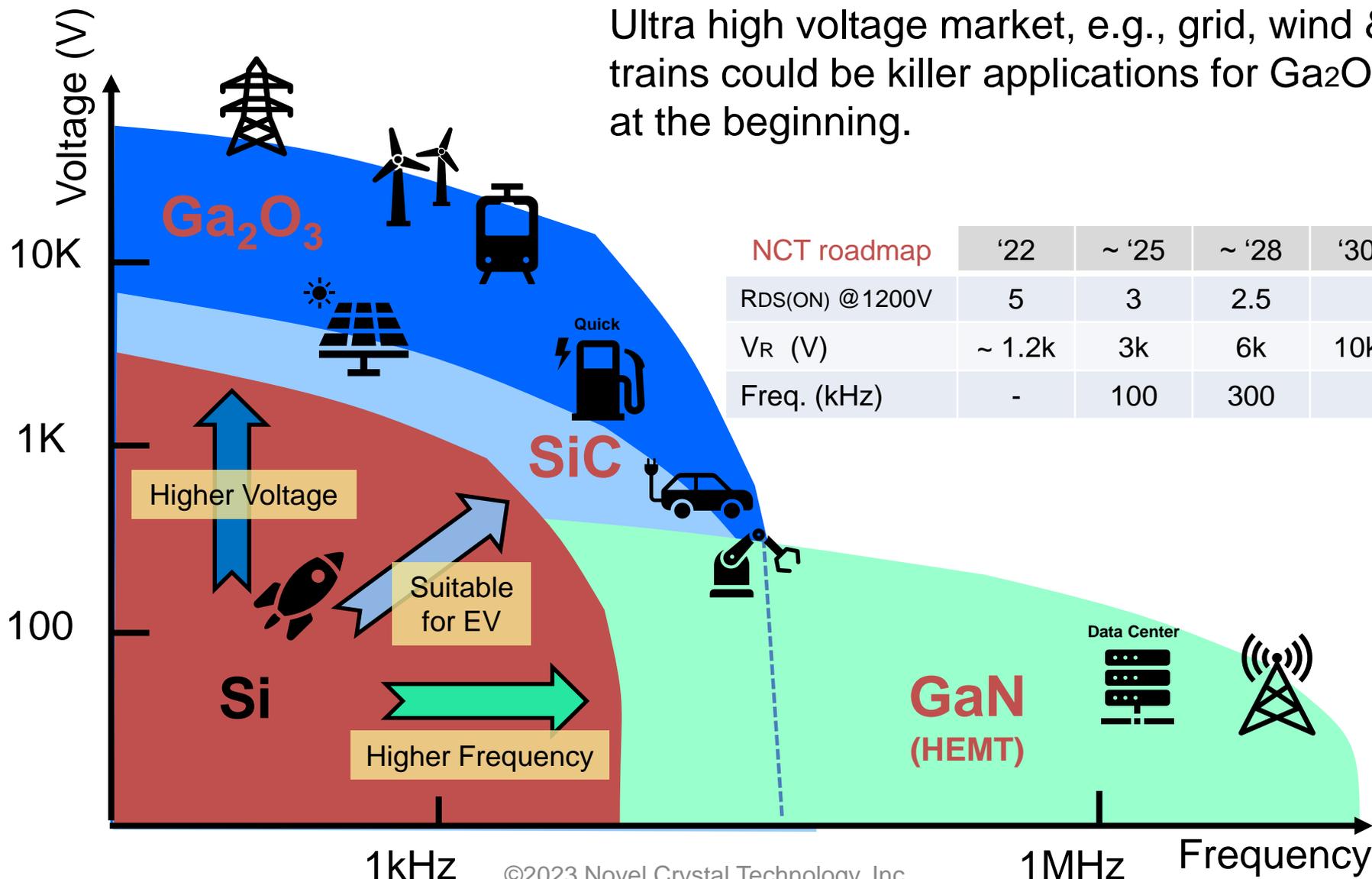
$\text{Ga}_2\text{O}_3$  bulk crystal



Crystal structure of  $\text{Ga}_2\text{O}_3$

# Applications

Ultra high voltage market, e.g., grid, wind & trains could be killer applications for Ga<sub>2</sub>O<sub>3</sub> at the beginning.



NCT roadmap	'22	~ '25	~ '28	'30 ~
RDS(ON) @1200V	5	3	2.5	
V <sub>R</sub> (V)	~ 1.2k	3k	6k	10k ~
Freq. (kHz)	-	100	300	

# Ga<sub>2</sub>O<sub>3</sub> Bulk Growth Methods

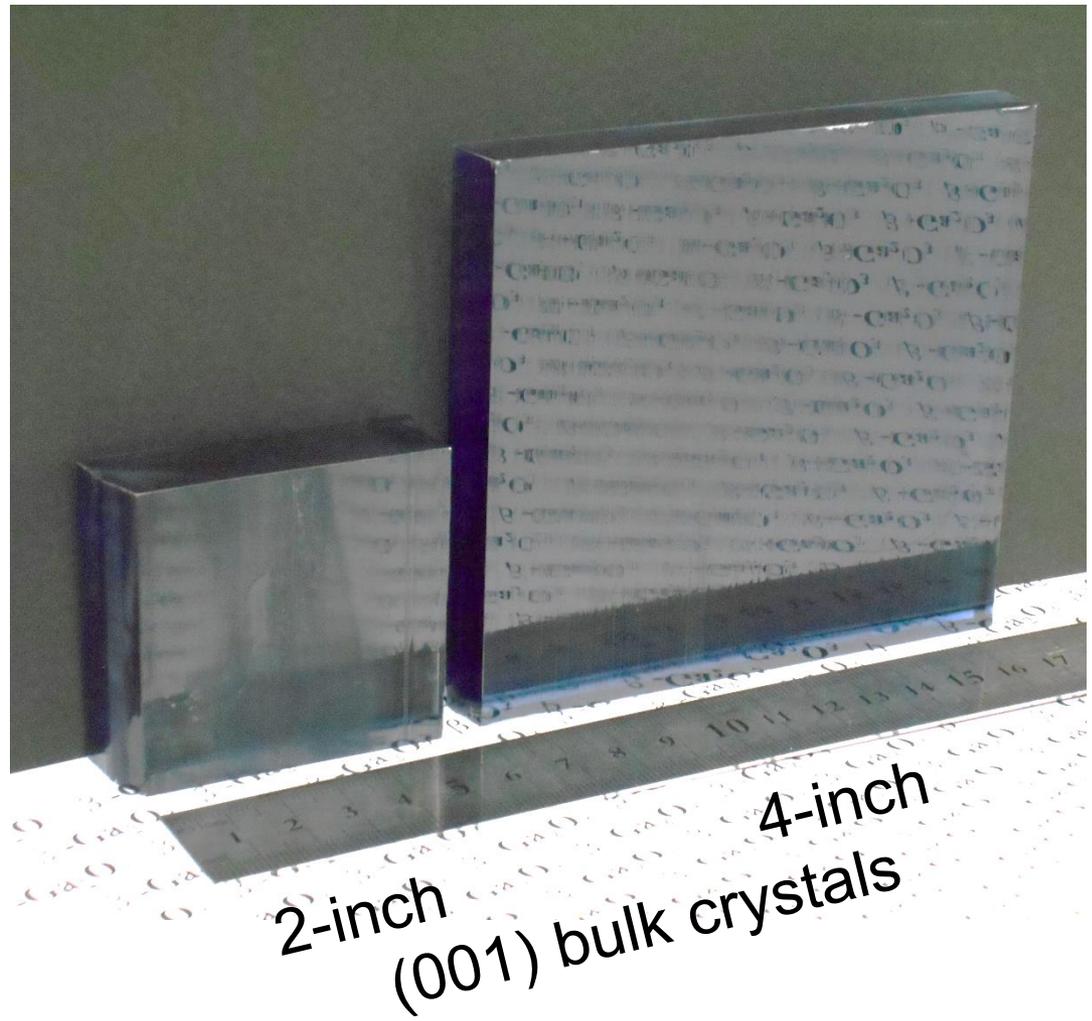
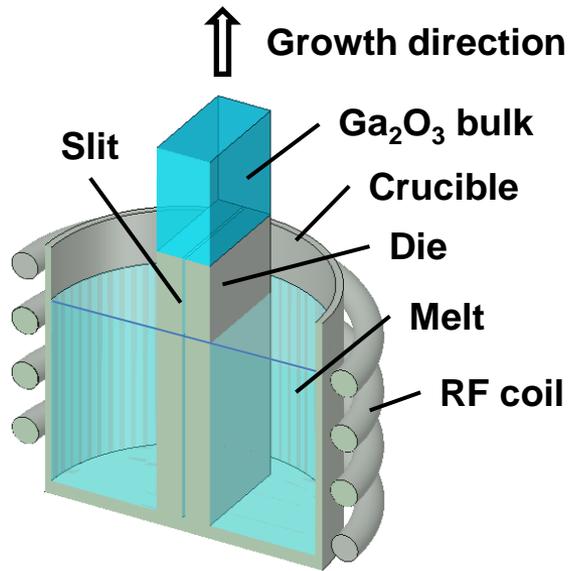


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Method	FZ	VB	CZ	EFG
<b>Bulk size reported</b>	<b>1 inch</b>	<b>2 inch</b>	<b>2 inch</b>	<b>6 inch</b>
<b>n-type doping</b>	<b>Possible</b>	<b>Possible</b>	<b>Possible</b>	<b>Possible</b>
<b>Growth rate (mm/h)</b>	<b>5</b>	<b>1</b>	<b>2</b>	<b>15</b>
<b>Strong point</b>	<b>High purity</b>	<b>High quality</b>	<b>Large boules</b>	<b>Large n-type</b>

# Edge-defined Film-fed Growth (EFG)

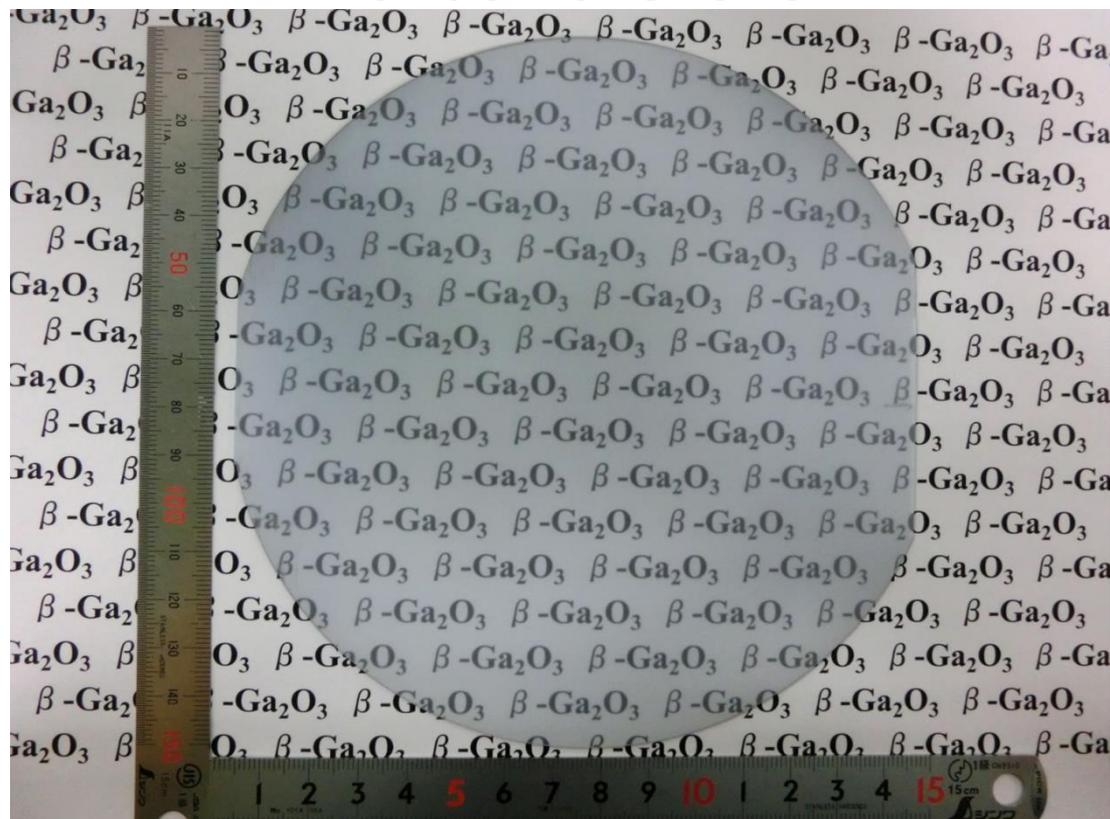
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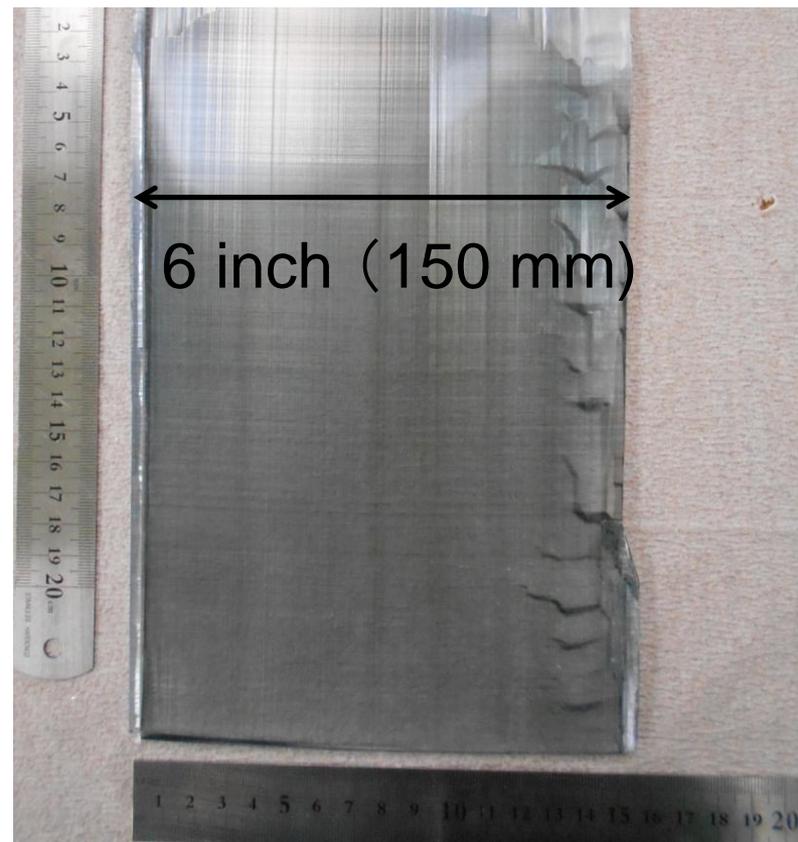
2-inch  
4-inch  
(001) bulk crystals

# 6-inch Substrates

For demonstration



**(001) 6-inch substrate**



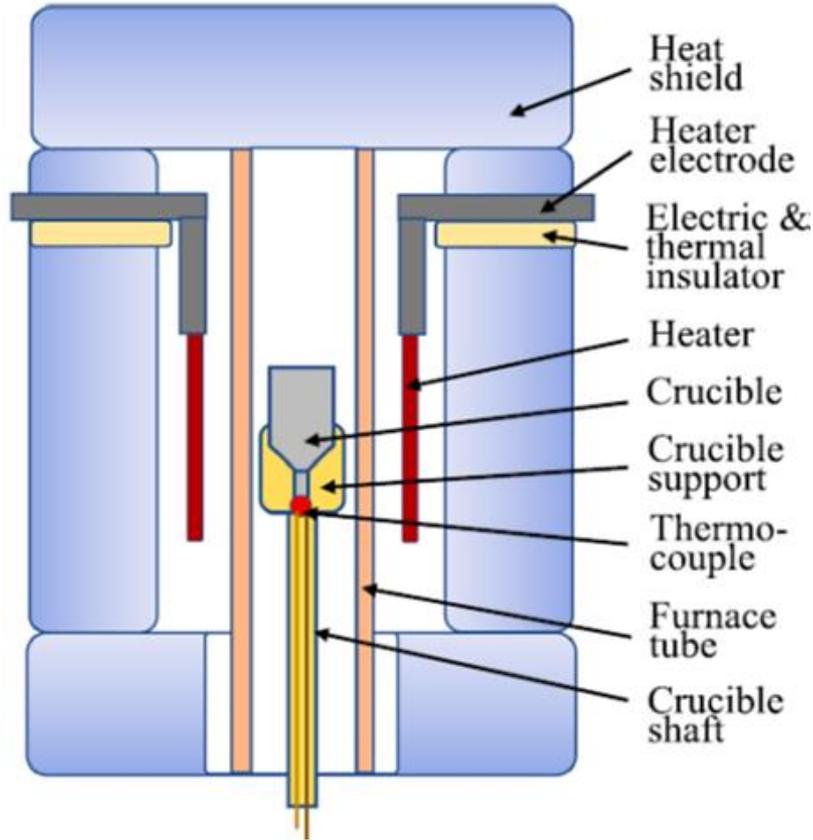
**(001) 6-inch bulk crystal**

There have been no commercial order for 6 inch substrates. But, once we get the order, we can quickly establish production of the 6-inch substrates.

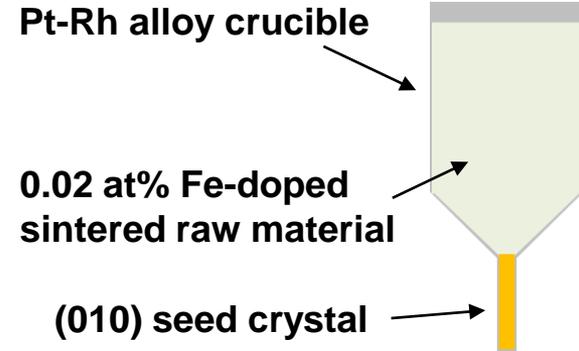
# Vertical Bridgman (VB)



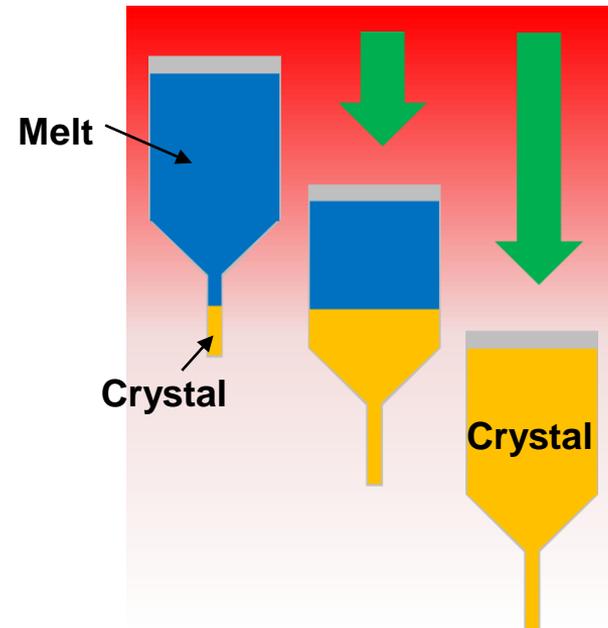
## Vertical Bridgman (VB)



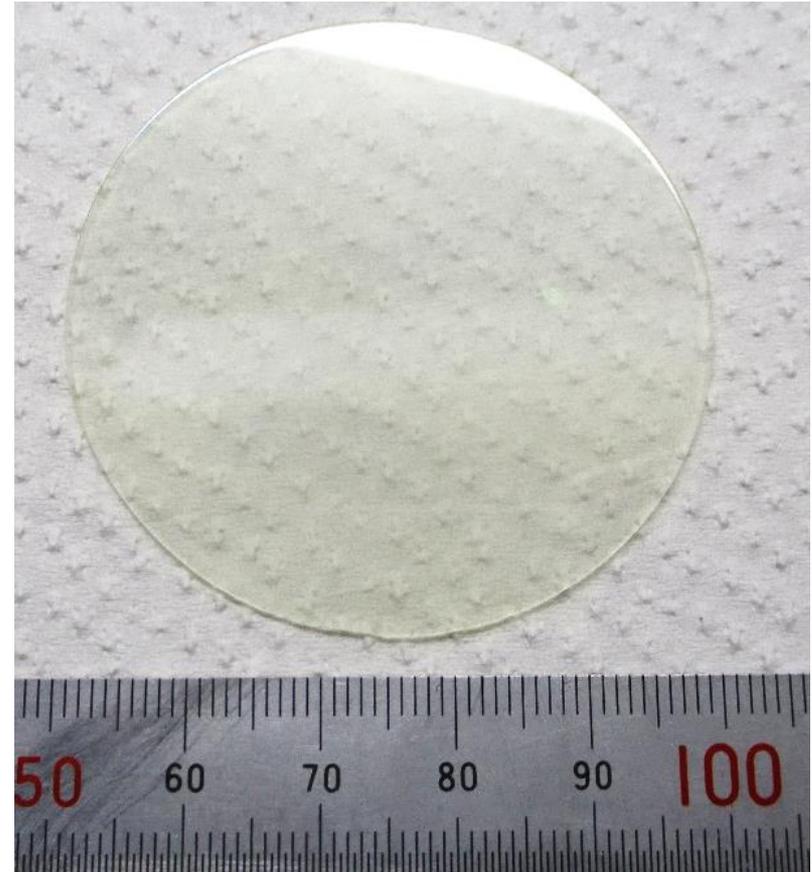
## Crucible



## Way to grow crystal



# Fe-doped 2-inch (010) Crystal



- Yellow coloration in the crystals origin to incorporation of Fe dopant and crucible-derived Rh
- **Successfully obtained 2-inch (010) substrates, the largest size (010) substrate ever reported**

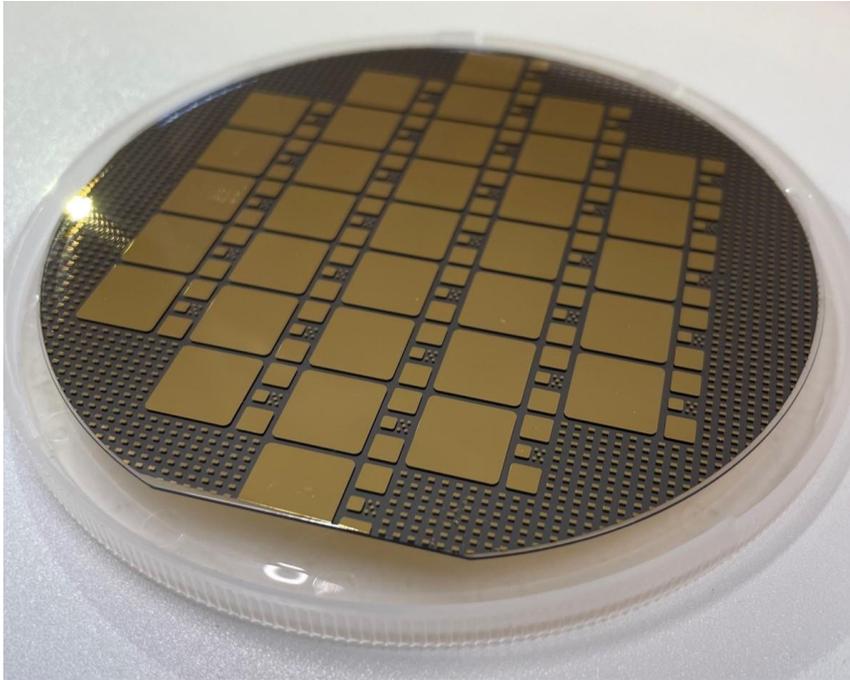


# 100-mm HVPE Epi Wafer

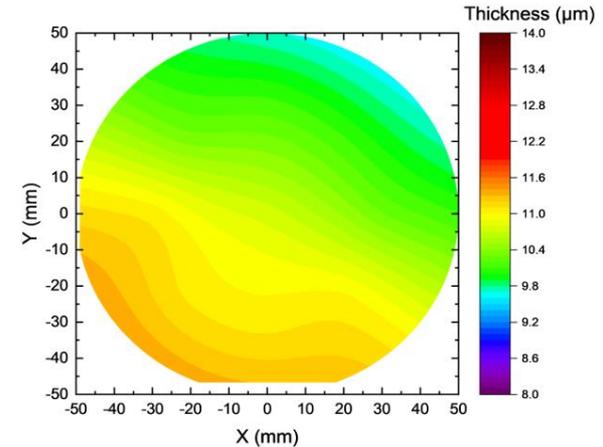


Novel Crystal Technology, Inc.

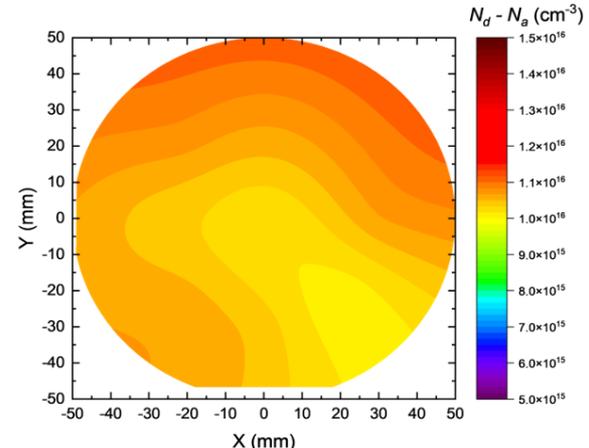
In collaboration with Saga University



100-mm  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> epitaxial wafer with SBD electrodes. Maximum chip size is 10 mm x 10 mm.



Film thickness distribution:  $10 \mu\text{m} \pm 5\%$



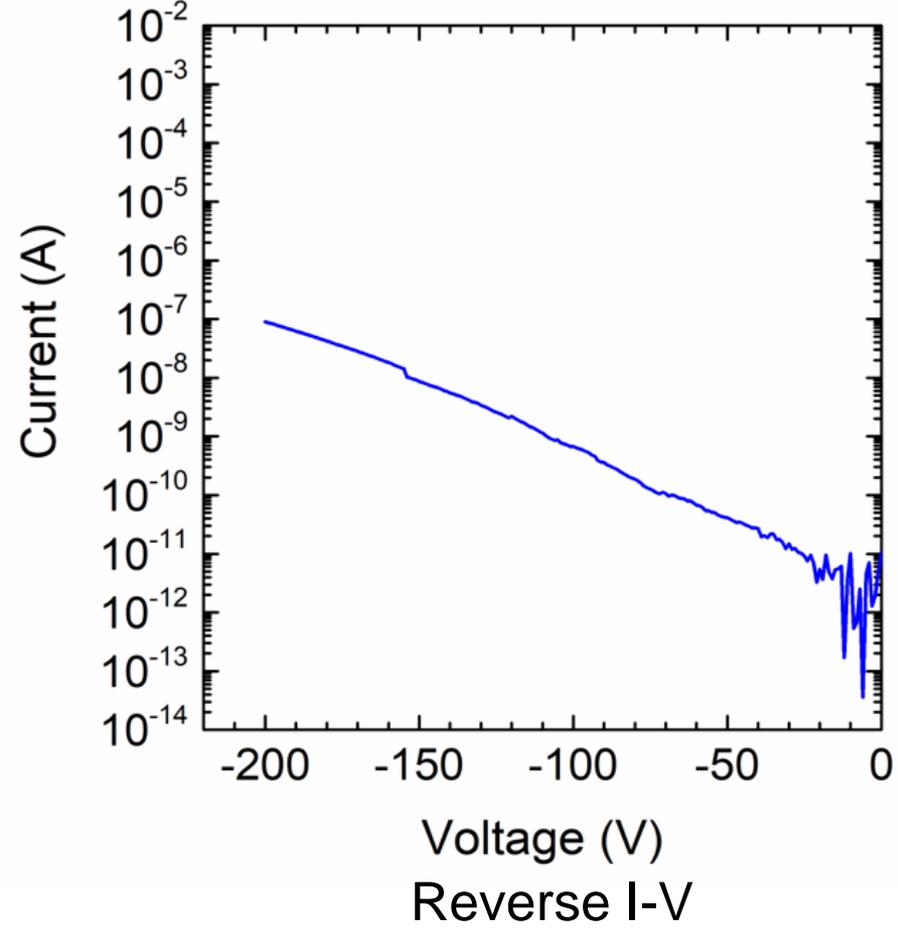
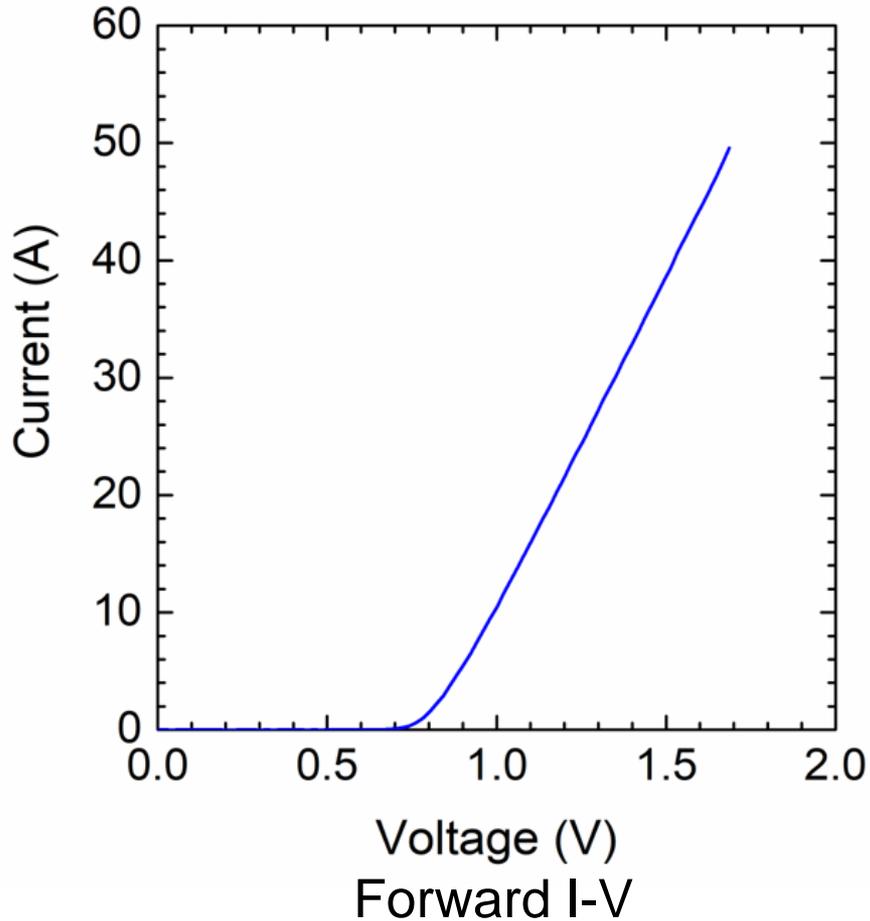
Donor concentration distribution:  
 $1 \times 10^{16} \text{ cm}^{-3} \pm 7\%$

We have developed 100-mm gallium oxide epitaxial wafers by using HVPE.



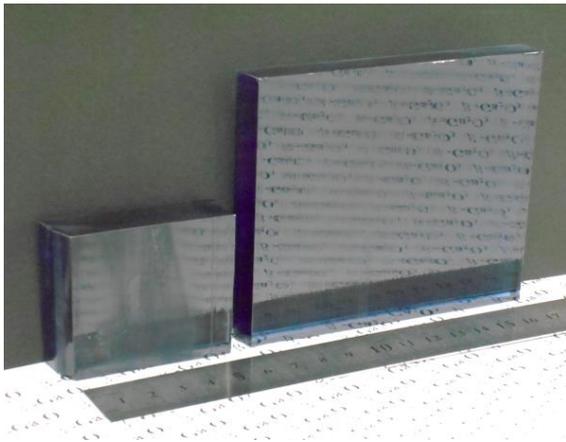
# 100-mm HVPE Epi Wafer

## 10 mm × 10 mm SBD



**The yield of the 10 mm × 10mm diodes was as high as 51%.  
The killer defect density is estimated to be about 0.7 cm<sup>-2</sup>.**

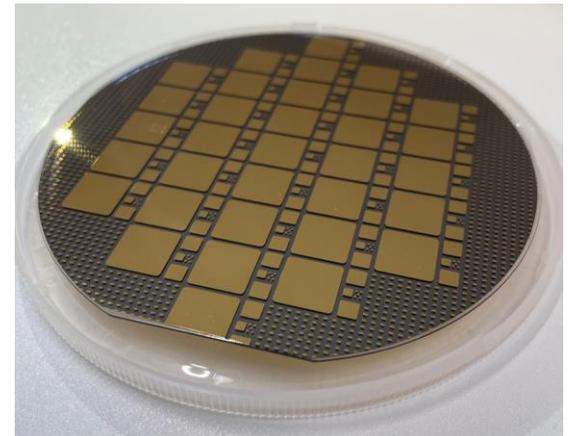
- ❖ **Ga<sub>2</sub>O<sub>3</sub> is a UWBG material for next generation power devices.**
- ❖ **Ga<sub>2</sub>O<sub>3</sub> covers the application area of high voltage.**
- ❖ **Large and high-quality native wafers are already commercially available.**



EFG Crystal



VB Crystal



HVPE epi wafer